



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

520.35237VX3

Applicants: KAJI et al.
Serial No.: 10/052,538
Filed: January 23, 2002
For: PLASMA PROCESSING APPARATUS PROCESSING METHOD
Group: 1763
Examiner: T. Dang

#6B
2/12/03
MW

AMENDMENT

Assistant Commissioner
for Patents
Washington, D.C. 20231

February 3, 2003

Sir:

In response to the Office Action dated October 3, 2002, the period of response for which extension is requested by the attached Petition for Extension of Time, please amend the above-identified application as follows:

In the Claims:

Please amend claims 17, 18, 23, 24, 25, 26 and 27 as follows:

17. (Amended) A plasma processing apparatus comprising:
- a pair of electrodes opposite to each other having a gap between the electrodes of 30 mm to 100 mm;
 - an electrostatic attracting means for holding a sample onto one of said electrodes by an electrostatic attracting force;
 - a gas introducing means for introducing an etching gas into an environment

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